

Title (en)
METHOD FOR PRODUCING MULTICRYSTALLINE SILICON

Title (de)
VERFAHREN ZUR HERSTELLUNG VON MULTIKRISTALLINEM SILICIUM

Title (fr)
PROCÉDÉ DE PRODUCTION DE SILICIUM POLYCRISTALLIN

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Application
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Abstract (en)
[origin: WO2016124509A1] The object of the invention is a method for producing multicrystalline silicon, comprising the following steps: providing a crucible for receiving a silicon melt, which comprises a bottom and an internal face, wherein at least the bottom of the crucible has a coating containing one or more compounds selected from the group consisting of Si₃N₄, oxidised Si₃N₄ and SiO₂; arranging a silicon layer in the crucible in contact with the coating of the bottom of the crucible; arranging polycrystalline silicon in the crucible in contact with the silicon layer; heating the crucible, until the polycrystalline silicon and silicon layer are completely melted to form a silicon melt; directional solidification of the silicon melt so as to result in a multicrystalline silicon block, characterised in that on heating the crucible and/or on melting the silicon layer, the silicon layer releases a reducing agent.

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